

ABSTRACT OF THE DISCLOSURE

An optical imprinting apparatus, and a method for producing a two-dimensional pattern, have line widths less than the wavelength of an exposure light. The evanescent (proximity) field effect is adopted to realize the apparatus and method. An optical imprinting apparatus comprises a container in which light is enclosed, an exposure-mask having a proximity field exposure pattern firmly fixed to a section of the container for exposing the exposure pattern on a photo-sensitive material through an evanescent field by the light enclosed therein; and a light source for supplying the light in the container.